

Origins of Spectral Diffusion in the Micro-Photoluminescence of Single InGaN Quantum Dots

B.P.L. Reid¹, T. Zhu², T.J. Puchtler², L.J. Fletcher², M.J. Kappers², C.C.S Chan¹, R.A. Oliver², R.A Taylor¹

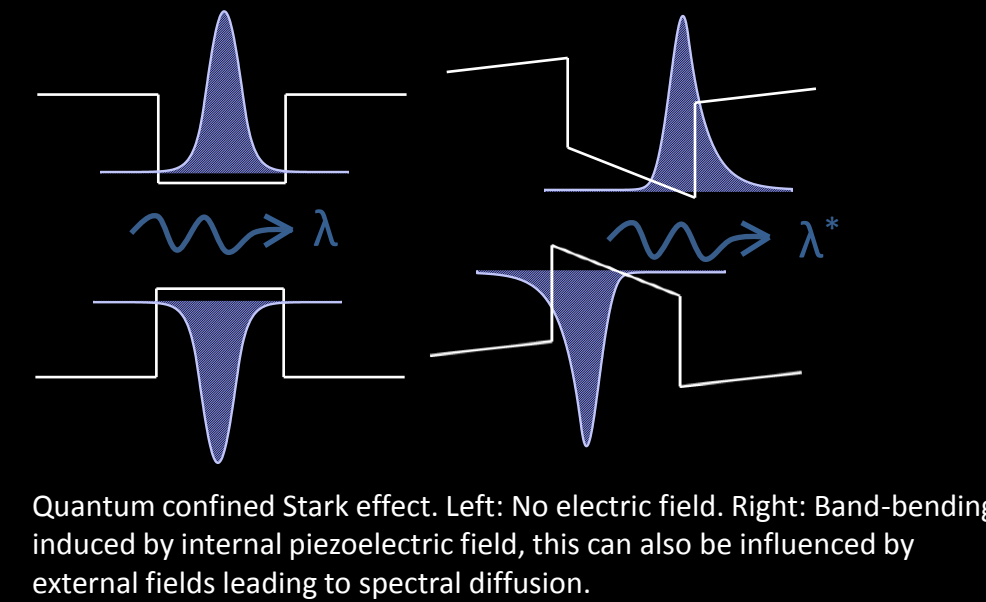
¹ Department of Physics, Clarendon Laboratory, University of Oxford, Parks Road, Oxford, OX1 3PU, UK.

² Department of Materials Science and Metallurgy, University of Cambridge, Pembroke Street, Cambridge, CB2 3QZ, UK.

1. Introduction

A coupled optical microcavity-quantum dot system achieved with InGaN quantum dots (QDs) could provide an electrically driven, tunable single photon source, a significant boon for the development of linear optical quantum computation and quantum cryptography systems.

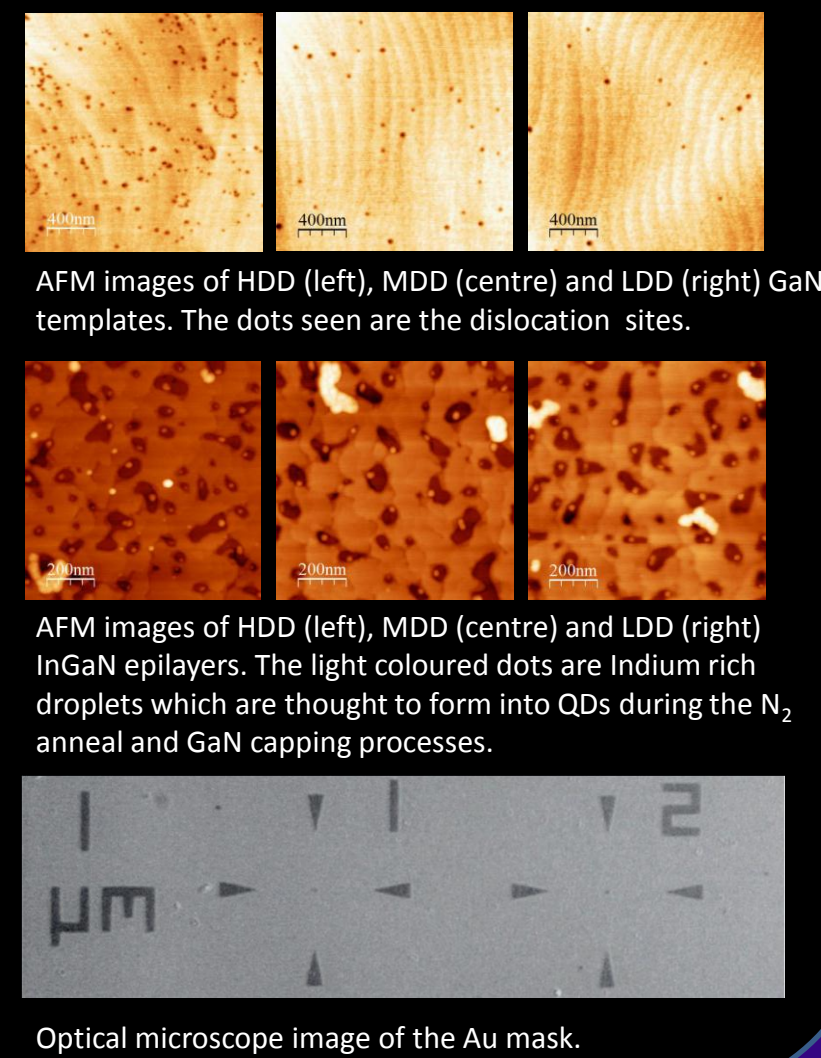
Micro-Photoluminescence measurements carried out on single InGaN quantum dots embedded in GaN show a significant temporal variation in the wavelength of the narrow ($\sim 300\mu\text{eV} - 3\text{meV}$) μPL peaks characteristic of QD emission. This is ascribed to Stark shifts induced by randomly generated local electric fields. An understanding of the causes of this “spectral diffusion”, and whether it can be overcome, is essential progress towards a coupled cavity-QD system, since temporal variation in emission wavelength of the QD would lead to a detuning from the cavity resonance.



2. Sample Growth & Preparation

Three GaN epilayers (shown right) with threading dislocation densities of $3.5 \times 10^8 \text{ cm}^{-2}$ (LDD), $8 \times 10^8 \text{ cm}^{-2}$ (MDD) and $6 \times 10^9 \text{ cm}^{-2}$ (HDD) were grown by metal-organic vapour phase at Cambridge university. QDs were formed on the different pseudo-substrates by the growth of a ca. 2.5nm InGaN epilayer which was then annealed in N_2 at the growth temperature, before being overgrown with a GaN cap. The InGaN epilayer is damaged by this process but still acts as a quantum well (QW). This growth process, termed “modified droplet epitaxy”, is still not fully understood.

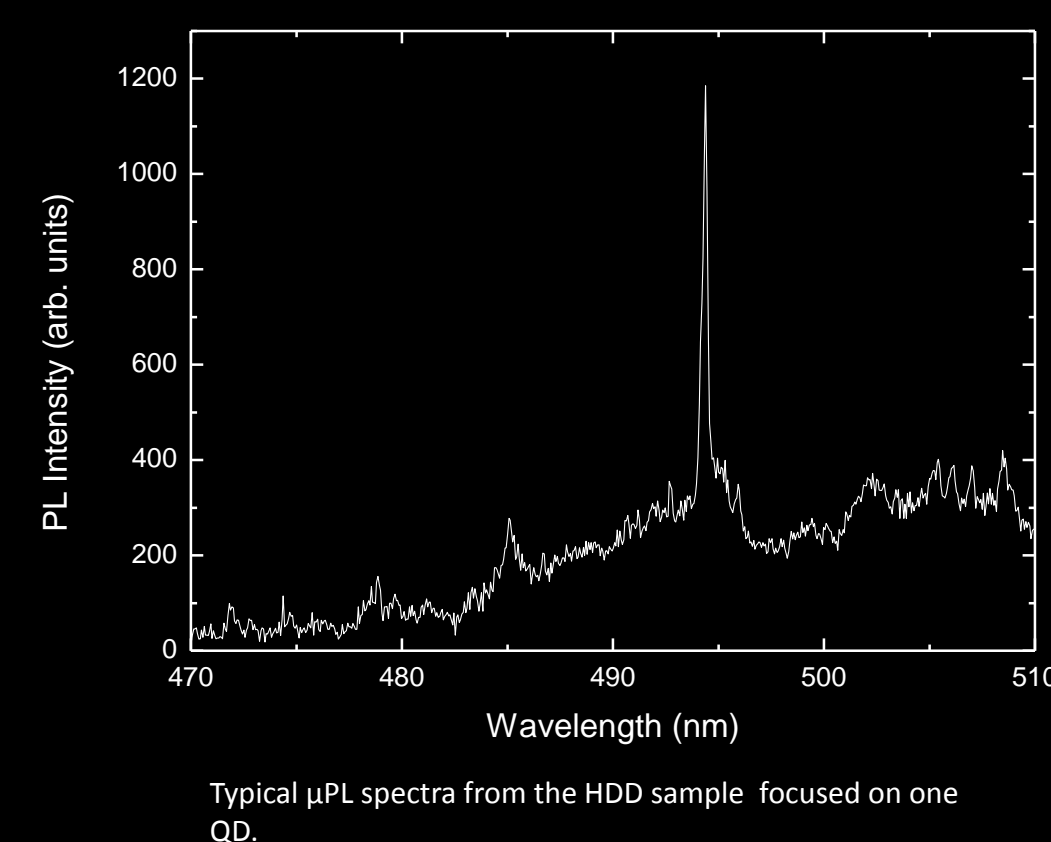
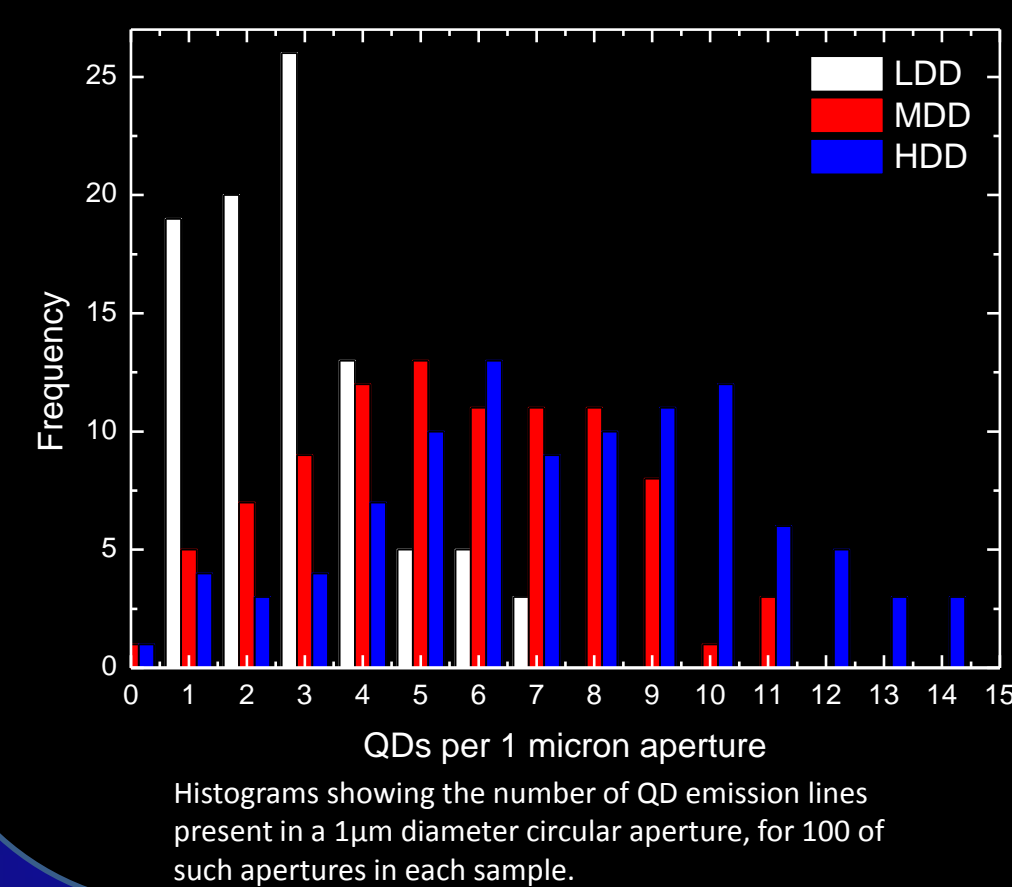
Each of the capped samples were masked with a pattern of $1\mu\text{m}$ diameter circular apertures using e-beam lithography and wet etching. This enables isolation of $\sim 0.8\mu\text{m}^2$ regions of each sample, meaning it's possible to isolate single QDs, and to return to a previously studied QD.



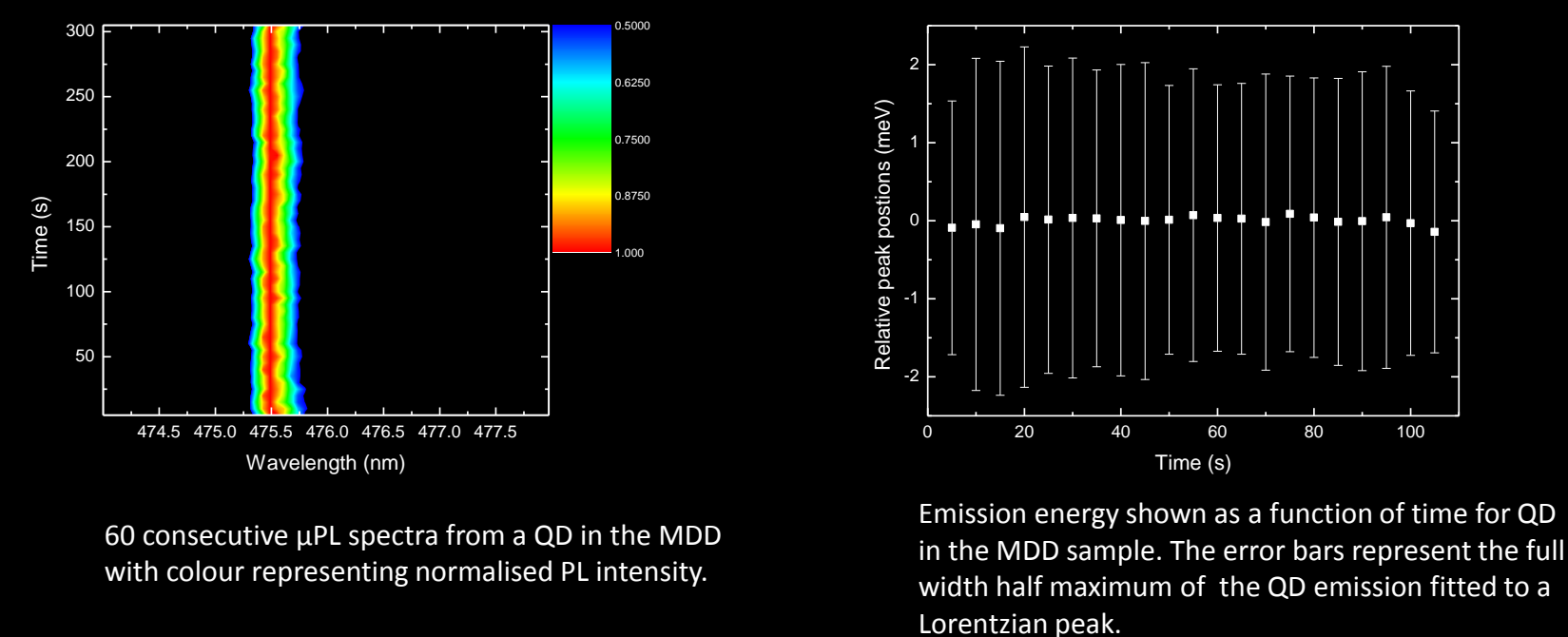
3. Micro-photoluminescence studies

Micro-photoluminescence measurements were performed using a two photon excitation technique, known to preferentially excite the 0D confined states of the QDs over that of the 2D confined QW, suppressing any background QW luminescence.

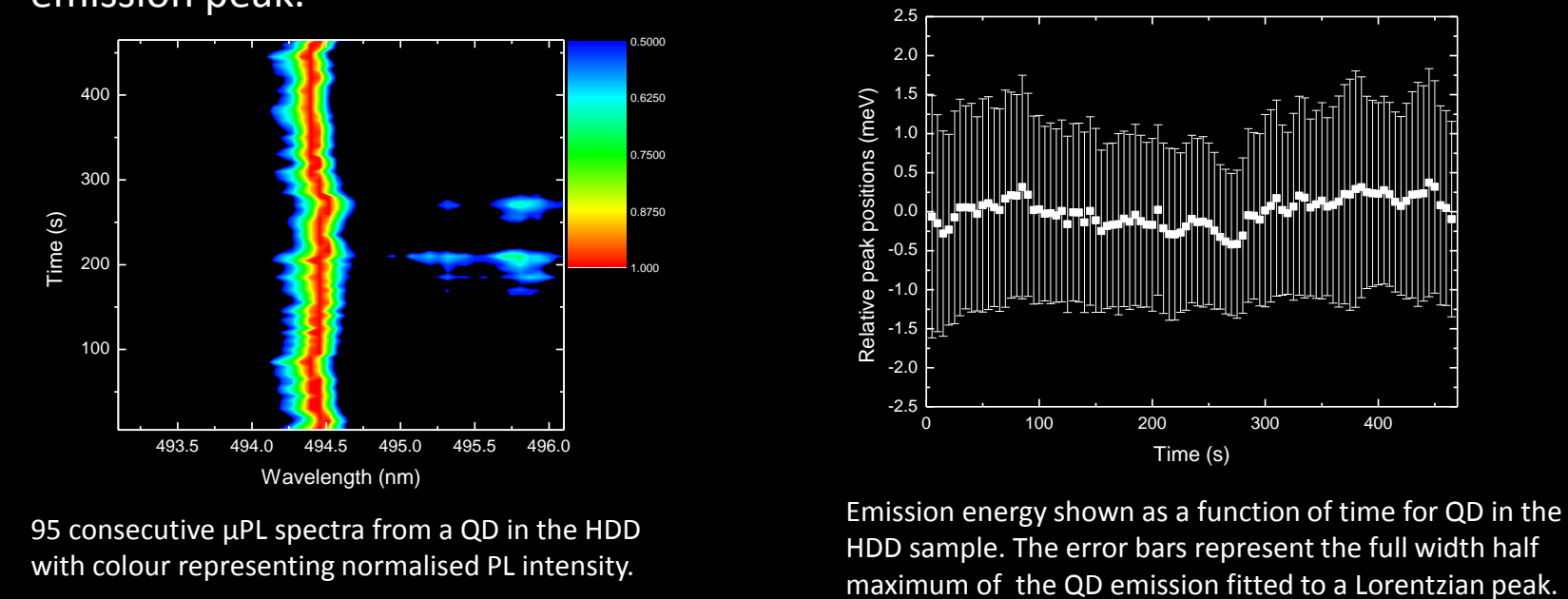
Low excitation power density ($\sim 1\text{MWcm}^{-2}$ 2-photon) studies were used to find the number of QD luminescence peaks per unit area, providing a metric for QD density. This metric was measured as $3.4 \times 10^8 \text{ cm}^{-2}$ (LDD), $6.4 \times 10^8 \text{ cm}^{-2}$ (MDD) and $9.5 \times 10^8 \text{ cm}^{-2}$ (HDD), in each case comparable to the dislocation density. This suggests that threading dislocations play a significant role in the formation of the QDs.



4. Temporal evolution of μPL

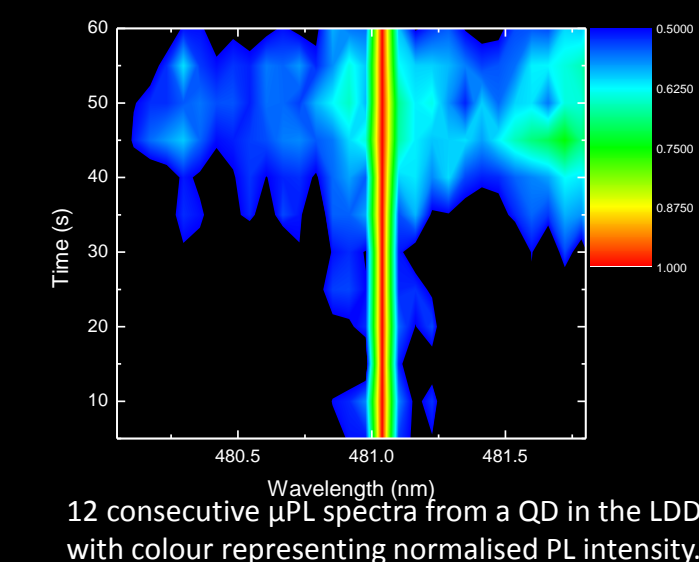


Typical time series results from the MDD sample are shown above. The change in QD emission energy with time is small compared to the QD linewidth (1.6meV). The linewidth is larger than expected for pure radiative decay from a QD, this is attributed to spectral diffusion processes on the timescale of nanoseconds artificially broadening the measured emission peak.



Typical time series results from the HDD sample are shown above. Temporal variations in the emission are much larger ($0.3\text{--}0.4\text{meV}$) relative to the QD linewidth (1.2meV). This variations are visible as “hops” in the μPL peak energy clearly visible over timescales of seconds. Since this long timescale spectral diffusion is much more common in the HDD sample than the LDD and MDD, it is attributed to non-radiative carrier traps at threading dislocation sites.

Statistically, the LDD sample shows the least evidence of spectral diffusion, with an example of a particularly well isolated dot shown to the right – spectral diffusion processes are occurring on a scale not observable within the resolution limit ($\sim 300\mu\text{eV}$) of the optical set-up.

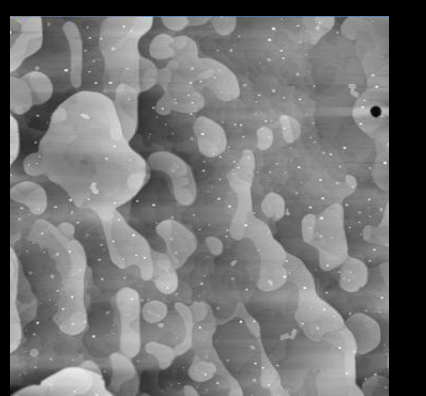


5. Summary

- QD formation is linked to threading dislocation sites
- Spectral diffusion processes occur in self-assembled InGaN QDs on two characteristic time scales: short (nanoseconds), and long (seconds)
- Long timescale spectral diffusion can be attributed to non-radiative carrier traps at threading dislocation sites.

6. Future Work

A new sample has been grown at Cambridge university (AFM right) using a thinner (1.2nm) InGaN epilayer and a prolonged N_2 anneal stage, in order to try to reduce the luminescence from the underlying QW layer. This should provide insight into the role of the QW, and whether carriers excited into the QW, or escaping from QD to QW are responsible for short timescale spectral diffusion.



AFM image of new sample with prolonged anneal time, the distribution of In droplets is more uniform.

Treatment of GaN pseudo-substrates with a SiH_4 flux has been found to increase dislocation pit width. Such a treated substrate will be used to grow InGaN QDs, which will then be masked in the normal way. Both μPL and AFM measurements in the same apertures will be used to investigate a correlation between the number of local dislocation pits and observed QD emission lines. If a correlation exists, using a dislocation pit as a marker for QD position would make spatial resonance between QD and optical microcavity relatively easy to achieve.